

=>

Connecting via Winsock to STN

Welcome to STN International! Enter x:X

LOGINID:ssptajqm1797

PASSWORD:

TERMINAL (ENTER 1, 2, 3, OR ?):2

NEWS 1		Web Page for STN Seminar Schedule - N. America
NEWS 2	DEC 01	ChemPort single article sales feature unavailable
NEWS 3	FEB 02	Simultaneous left and right truncation (SLART) added for CERAB, COMPUAB, ELCOM, and SOLIDSTATE
NEWS 4	FEB 02	GENBANK enhanced with SET PLURALS and SET SPELLING
NEWS 5	FEB 06	Patent sequence location (PSL) data added to USGENE
NEWS 6	FEB 10	COMPENDEX reloaded and enhanced
NEWS 7	FEB 11	WTEXTILES reloaded and enhanced
NEWS 8	FEB 19	New patent-examiner citations in 300,000 CA/CAplus patent records provide insights into related prior art
NEWS 9	FEB 19	Increase the precision of your patent queries -- use terms from the IPC Thesaurus, Version 2009.01
NEWS 10	FEB 23	Several formats for image display and print options discontinued in USPATFULL and USPAT2
NEWS 11	FEB 23	MEDLINE now offers more precise author group fields and 2009 MeSH terms
NEWS 12	FEB 23	TOXCENTER updates mirror those of MEDLINE - more precise author group fields and 2009 MeSH terms
NEWS 13	FEB 23	Three million new patent records blast AEROSPACE into STN patent clusters
NEWS 14	FEB 25	USGENE enhanced with patent family and legal status display data from INPADOCDB
NEWS 15	MAR 06	INPADOCDB and INPAFAMDB enhanced with new display formats
NEWS 16	MAR 11	EPFULL backfile enhanced with additional full-text applications and grants
NEWS 17	MAR 11	ESBIOBASE reloaded and enhanced
NEWS 18	MAR 20	CAS databases on STN enhanced with new super role for nanomaterial substances
NEWS 19	MAR 23	CA/CAplus enhanced with more than 250,000 patent equivalents from China
NEWS 20	MAR 30	IMSPATENTS reloaded and enhanced
NEWS 21	APR 03	CAS coverage of exemplified prophetic substances enhanced
NEWS 22	APR 07	STN is raising the limits on saved answers
NEWS 23	APR 24	CA/CAplus now has more comprehensive patent assignee information
NEWS 24	APR 26	USPATFULL and USPAT2 enhanced with patent assignment/reassignment information
NEWS 25	APR 28	CAS patent authority coverage expanded
NEWS 26	APR 28	ENCOMPLIT/ENCOMPLIT2 search fields enhanced
NEWS 27	APR 28	Limits doubled for structure searching in CAS REGISTRY

NEWS EXPRESS JUNE 27 08 CURRENT WINDOWS VERSION IS V8.3.

AND CURRENT DISCOVER FILE IS DATED 23 JUNE 2008.

NEWS HOURS STN Operating Hours Plus Help Desk Availability
NEWS LOGIN Welcome Banner and News Items

Enter NEWS followed by the item number or name to see news on that specific topic.

All use of STN is subject to the provisions of the STN customer agreement. This agreement limits use to scientific research. Use for software development or design, implementation of commercial gateways, or use of CAS and STN data in the building of commercial products is prohibited and may result in loss of user privileges and other penalties.

FILE 'HOME' ENTERED AT 09:50:25 ON 07 MAY 2009

=> file caplus
COST IN U.S. DOLLARS
SINCE FILE
ENTRY
TOTAL
SESSION
0.22
0.22
FULL ESTIMATED COST

FILE 'CAPLUS' ENTERED AT 09:50:34 ON 07 MAY 2009
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
COPYRIGHT (C) 2009 AMERICAN CHEMICAL SOCIETY (ACS)

Copyright of the articles to which records in this database refer is held by the publishers listed in the PUBLISHER (PB) field (available for records published or updated in Chemical Abstracts after December 26, 1996), unless otherwise indicated in the original publications. The CA Lexicon is the copyrighted intellectual property of the American Chemical Society and is provided to assist you in searching databases on STN. Any dissemination, distribution, copying, or storing of this information, without the prior written consent of CAS, is strictly prohibited.

FILE COVERS 1907 - 7 May 2009 VOL 150 ISS 19
FILE LAST UPDATED: 6 May 2009 (20090506/ED)
REVISED CLASS FIELDS (/NCL) LAST RELOADED: Feb 2009
USPTO MANUAL OF CLASSIFICATIONS THESAURUS ISSUE DATE: Feb 2009

CPlus now includes complete International Patent Classification (IPC) reclassification data for the third quarter of 2008.

CAS Information Use Policies apply and are available at: www.cas.org/cas-information-use-policies

<http://www.cas.org/legal/infopolicy.html>

This file contains CAS Registry Numbers for easy and accurate

```
=> s (hermetic? or leak?) and (mems or moems or micrometric) and py<=2004
    14143 HERMETIC?
    125618 LEAK?
    12648 MEMS
        353 MOEMS
    1317 MICROMETRIC
        9 MICROMETRICS
    1326 MICROMETRIC
```

(MICROMETRIC OR MICROMETRICS)

25140108 PY<=2004

L1 196 (HERMETIC? OR LEAK?) AND (MEMS OR MOEMS OR MICROMETRIC) AND PY<=2004

=> s l1 and (optic? or visual?)

1222552 OPTIC?

152386 VISUAL?

L2 30 L1 AND (OPTIC? OR VISUAL?)

=> d l2 1-30 ibib abs

L2 ANSWER 1 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2005:941300 CAPLUS
 DOCUMENT NUMBER: 143:469098
 TITLE: Monolithic suspended optical waveguides for InP MEMS
 AUTHOR(S): Kelly, Daniel P.; Pruesner, Marcel W.; Amarnath, Kuldeep; Datta, Madhumita; Kanakaraju, S.; Calhoun, Lynn C.; Ghodssi, Reza
 CORPORATE SOURCE: Department of Electrical and Computer Engineering, Institute for Systems Research, University of Maryland, College Park, MD, 20740, USA
 SOURCE: IEEE Photonics Technology Letters (2004), 16(5), 1298-1300
 CODEN: IPTLEL; ISSN: 1041-1135
 PUBLISHER: Institute of Electrical and Electronics Engineers
 DOCUMENT TYPE: Journal
 LANGUAGE: English
 AB We present a novel waveguide design for InP microelectromechanical systems. The substrate is removed from underneath the waveguide by sacrificial etching, and the suspended waveguide is supported by lateral tethers. This allows segments of the waveguide to be moved and prevents substrate leakage loss in the fixed segments of the waveguides. A single-mask fabrication process is developed that can be extended to more complex devices employing electrostatic actuation. Fabricated suspended waveguides exhibit a loss of 2.2 dB/cm and tether pairs exhibit 0.25-dB addnl. loss.

REFERENCE COUNT: 5 THERE ARE 5 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 2 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2005:303321 CAPLUS
 DOCUMENT NUMBER: 142:363946
 TITLE: Methods for depositing, releasing and packaging micro-electromechanical devices on wafer substrates
 INVENTOR(S): Patel, Satayadev R.; Huibers, Andrew G.; Chiang, Steve; Duboc, Robert M.; Grobelsky, Thomas J.; Chen, Hung Nam; Dehlinger, Dietrich; Richards, Peter W.; Shi, Hongqin; Sun, Anthony Reflectivity, Inc., USA
 PATENT ASSIGNEE(S): U.S. Pat. Appl. Publ., 25 pp., Cont.-in-part of U.S. Ser. No. 5,308.
 SOURCE: CODEN: USXXCO
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 20
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE	
US 20050074919	A1	20050407	US 2002-167361	20020611	
US 7307775	B2	20071211			
US 20030054588	A1	20030320	US 2001-5308	20011203	
US 6969635	B2	20051129			
AU 2002250322	A1	20021003	AU 2002-250322	20020315	
WO 2003105198	A1	20031218	WO 2003-US18741	20030611	
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GR, HU, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KE, LC, LK, LR, LS, LT, LU, LV, MA, MD, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, VN, YU, ZA, ZM, ZW	AU 2003263744	A1	20031222	AU 2003-263744	20030611
CN 1659684	A	20050824	CN 2003-813553	20030611	
JP 20055340408	T	20051110	JP 2004-512176	20030611	
EP 1766663	A1	20070328	EP 2003-817376	20030611	
R: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LI, LU, MC, NL, PT, RO, SE, SI, SK, TR	WO 2004093083	A2	20041028	WO 2004-US9221	20040324
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GR, HU, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KE, LC, LK, LR, LS, LT, LU, LV, MA, MD, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, VN, YU, ZA, ZM, ZW	WO 2004093083	A3	20050609		
RW: BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG	EP 1611581	A2	20060104	EP 2004-758968	20040324
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK	CN 1784748	A	20060607	CN 2004-80012015	20040324

L2 ANSWER 2 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN (Continued)
 US 20050042792 A1 20050224 US 2004-930342 20040830
 US 6950034 B2 20060207
 US 20050048688 A1 20050303 US 2004-930450 20040830
 US 20050139940 A1 20050630 US 2005-70036 20050301
 US 20050170540 A1 20050804 US 2005-93550 20050329
 US 7139982 B2 20070403
 US 20050170614 A1 20050804 US 2005-93927 20050329
 US 7449358 B2 20081111
 US 20050170557 A1 20050804 US 2005-93942 20050329
 US 20050170547 A1 20050804 US 2005-93943 20050329
 US 6950040 B2 20060207
 US 20050173711 A1 20050811 US 2005-94087 20050329
 US 20050181532 A1 20050818 US 2005-102183 20050407
 US 20050179982 A1 20050818 US 2005-102187 20050407
 US 20050191789 A1 20050901 US 2005-102291 20050407
 US 20050191790 A1 20050901 US 2005-102295 20050407
 US 20050214976 A1 20050939 US 2005-102108 20050407
 US 20050260792 A1 20051124 US 2005-102204 20050407
 US 7262878 B2 20071023
 US 20050260793 A1 20051124 US 2005-102214 20050407
 US 20070001247 A1 20070104 US 2005-101939 20050407
 US 20080096313 A1 20080424 US 2007-954076 20071211
 PRIORITY APPLN. INFO.: US 2000-254043P P 20010207
 US 2001-276222P P 20010315
 US 2001-5308 A2 20011203
 WO 2002-US7761 W 20020315
 US 2002-167361 A 20020611
 US 2003-407061 A 20030402
 WO 2003-US18741 W 20030611
 WO 2004-US9221 W 20040324

AB A projection system, a spatial light modulator, and a method for forming a MEMS device is disclosed. The spatial light modulator can have two substrates bonded together with one of the substrates comprising a micromirror array. The two substrates can be bonded at the wafer level after depositing a getter material and/or solid or liquid lubricant on one or both of the wafers. The wafers can be bonded together hermetically if desired, and the pressure between the two substrates can be below atmospheric
 REFERENCE COUNT: 86 THERE ARE 86 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 3 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2005:271330 CAPLUS
 DOCUMENT NUMBER: 142:344864
 TITLE: Method of sealing a hermetic lid to a semiconductor die at an angle
 INVENTOR(S): Leung, Omar S.
 PATENT ASSIGNEE(S): Silicon Light Machines Corporation, USA
 SOURCE: U.S., 27 pp., Cont.-in-part of U.S. Ser. No. 866,266.
 CODEN: USXXAM
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 2
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 6072984	B1	20050329	US 2002-179664	20020624
US 6303986	B1	20011016	US 1998-124710	19980729
US 20010022382	A1	20010920	US 2001-866266	20010524
US 6764875	B2	20040720		
PRIORITY APPLN. INFO.:			US 1998-124710	A3 19980729
			US 2000-605198	B2 20000627
			US 2001-866266	A2 20010524

AB The current invention provides a optical MEMS device and system with an angled lid for hermetically sealing an active MEMS structure. The lid is sealed through an asym. seal formed with sealing rings having an asym. distribution of solder wetting surfaces which tilts the lid, when the lid and a substrate are soldered together. The asym. distribution wetting surfaces can be provided by forming one or more edge features, by patterning portions of the sealing rings or both. Preferably, the lid is transparent to one or more wavelengths of light at 300-3000 Å and hermetically seals a grating light valve structure having a plurality of movable ribbon for modulating light through the lid.

REFERENCE COUNT: 969 THERE ARE 969 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 4 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2005:87926 CAPLUS
 DOCUMENT NUMBER: 143:335680
 TITLE: Conducting antireflection coatings with low polarization dependent loss for telecommunication applications
 AUTHOR(S): Dobrowolski, J. A.; Ford, Joseph E.; Sullivan, Brian T.; Lu, Liping; Osborne, Norman R.
 CORPORATE SOURCE: Institute for Microstructural Sciences, National Research Council of Canada, Ottawa, ON, K1A 0R6, Can.
 SOURCE: Optics Express (2004), 12(25), 6258-6269
 CODEN: OPEXFF; ISSN: 1094-4087
 URL: http://www.opticsexpress.org/view_file.cfm?doc=%204%29%2C%3B%2B%20%20%0A&id=%25%28%2C%2B%27%5C%5C%20%20
 OA
 PUBLISHER: Optical Society of America
 DOCUMENT TYPE: Journal; (online computer file)
 LANGUAGE: English
 AB Conducting optical coatings for the visible light range are commonly made of In Sn Oxide (ITO), but ITO is unsuitable for near-IR telecommunications wavelengths because it can become absorptive after extended illumination. The authors show an alternative approach which uses conventional coating materials to create either nonconducting or conducting antireflection (AR) coatings that are effective over a fairly broad spectral region ($\lambda_{long}/\lambda_{short} \approx 1.40$) and also usable for a wide range of angles of incidence (0-38°, or 0-55°) in the telecom wavelength range. Not only is the transmittance of windows treated with such coatings quite high, but they can be made to have extreme polarization independence (low polarization dependent loss values). A number of such coating designs are presented.
 A prototype of one of the conducting AR coating designs was fabricated and the measurements are in reasonable agreement with the calculated performance. Such AR coatings should be of interest for telecommunication applications and especially for antistatic hermetic packaging of MEMS devices such as optical switches.
 REFERENCE COUNT: 11 THERE ARE 11 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE REFORMAT

L2 ANSWER 5 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2004:436641 CAPLUS
 DOCUMENT NUMBER: 141:132343
 TITLE: Localized, in-situ vacuum measurements for MEMS packaging
 AUTHOR(S): Moelders, Nicholas; Daly, James T.; Greenwald, Anton C.; Johnson, Edward A.; McNeal, Mark P.; Patel, Ramesh; Pralle, Martin U.; Puscasu, Irina Ion Optics, Inc., Waltham, MA, USA
 CORPORATE SOURCE: Materials Research Society Symposium Proceedings (2004), Volume Date 2003, 782(Micro- and Nanosystems), 211-215
 SOURCE: CODEN: MRSPDH; ISSN: 0272-9172
 PUBLISHER: Materials Research Society
 DOCUMENT TYPE: Journal
 LANGUAGE: English
 AB MEMS devices have unique packaging considerations compared to conventional semiconductor devices. They tend to have relatively large die size and many architectures cannot tolerate elevated temps. Often these devices require a vacuum environment for efficient operation. While advances were made in hermetic packaging of MEMS devices, vacuum packaging remains elusive. One significant problem in developing vacuum sealing was the inability to determine, readily and nondestructively, the vacuum level inside the package. The authors have previously described the development of a Si MEMS-based chip design, SensorChip, with integrated photonic crystal and reflective optics, which uses narrow-band optical emission and absorption for selective identification of gas and chemical species. Because the power consumption required to maintain a specific temperature is directly related to the vacuum level, these devices effectively serve as microscopic Pirani gauges - local vacuum sensors in the moderate vacuum range (0.01 to 1.0 torr) of interest to MEMS devices. Using the membrane itself as a vacuum gauge during sealing proved to be an invaluable tool in developing a robust vacuum seal in a leadless chip carrier package. It has enabled the authors to optimize choice of design, materials and processing.
 REFERENCE COUNT: 4 THERE ARE 4 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE REFORMAT

L2 ANSWER 6 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2004:244700 CAPLUS
 TITLE: Light activated switch and the production method [Machine Translation].
 INVENTOR(S): Maeda, Hidekata; Kato, Kenji
 PATENT ASSIGNEE(S): Seiko Instruments, Inc., Japan
 SOURCE: Jpn Kokai Tokkyo Koho, 11 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004094089	A	20040325	JP 2002-257596	20020903
<-- PRIORITY APPLN. INFO.: JP 2002-257596 20020903				

 AB [Machine Translation of Descriptors]. Switching operation is made secure and high speed in the light activated switch which is produced minutely making use of MEMS technology, electric power consumption small the paragraph and leakage flux are made small with operational efficiency as satisfactory. In lower part baseplate 11, it forms simultaneously the 1st V groove concave section 23a of 12 for optical fiber fixing and laminated spring positioning expedient 23, with etching. And, movable optical fiber inside 1st V groove 12, positioning laminated spring 13 in concave section 23a, it locks 16 and fixed optical fiber 26 respectively. Positioning time being categorized 15 to concave section 21a of concave section 11a of lower part baseplate 11 and upper baseplate 21, the alignment doing both baseplates 11,21, it locks mutually. One fixed optical fiber 26 is locked already inside 2nd V groove 22 of upper baseplate 21. Then, in the surface of upper baseplate 21 making the portion of electromagnet 18 the electromagnet positioning concave section fit 25 which, is formed by etching positioning, it locks.

L2 ANSWER 7 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2004:210909 CAPLUS
 DOCUMENT NUMBER: 141:339961
 TITLE: Total dose degradation of MEMS optical mirrors
 AUTHOR(S): Miyahira, T. F.; Becker, H. N.; McClure, S. S.; Edmonds, L. D.; Johnston, A. H.; Hishinuma, Y.
 CORPORATE SOURCE: Jet Propulsion Laboratory, California Institute of Technology, Pasadena, CA, USA
 SOURCE: IEEE Transactions on Nuclear Science (2003), 50(6, Pt. 1), 1860-1866
 CODEN: IETNAE; ISSN: 0018-9499
 PUBLISHER: Institute of Electrical and Electronics Engineers
 DOCUMENT TYPE: Journal
 LANGUAGE: English
 AB This paper discusses the effect of ionizing radiation on two types of deformable MEMS mirrors. Little effect was observed in the technol. that was based on electrostatic deflection, consistent with the structural design that does not contain insulators between the two sections. Significant changes in the operating characteristics were observed for the 2nd type of mirror, which uses piezoelec. material for actuation. The mirrors required higher total dose levels before they were affected compared with MEMS accelerometers, which can be explained by the larger interelement spacing used in the mirror arrays.
 REFERENCE COUNT: 11 THERE ARE 11 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE REFORMAT

L2 ANSWER 8 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2004165938 CAPLUS
 DOCUMENT NUMBER: 141:15019
 TITLE: Sealing of adhesive bonded devices on wafer level
 AUTHOR(S): Oberhammer, J.; Niklaus, F.; Stemme, G.
 CORPORATE SOURCE: Microsystem Technology, Sensors and Systems, Department of Signals, Royal Institute of Technology (KTH), Stockholm, SE-10044, Swed.
 SOURCE: Sensors and Actuators, A: Physical (2004), A110(1-3), 407-412
 CODEN: SAAPB; ISSN: 0924-4247
 PUBLISHER: Elsevier Science B.V.
 DOCUMENT TYPE: Journal
 LANGUAGE: English
 AB In this paper, we present a low temperature wafer-level encapsulation technique to hermetically seal adhesive bonded microsystem structures by cladding the adhesive with an addnl. diffusion barrier. Two wafers containing cavities for MEMS devices were bonded together using benzocyclobutene (BCB). The devices were sealed by a combined dicing and self-aligning etching technique and by finally coating the structures with evaporated gold or PECVD silicon nitride. The sealing layer was inspected visually by SEM and helium leak tests were carried out. Devices sealed with silicon nitride and with known damage of the sealing layer showed a helium leak rate of .apprx.7-14 times higher than the background level. Devices of the same size without damage in the sealing layer had a leak rate of only 1.3 times higher than the background level. Expts. with evaporated gold as cladding layer revealed leaking cracks in the film even up to a gold thickness of 5 μ m. The sealing technique with silicon nitride shows a significant improvement of the hermeticity properties of adhesive bonded cavities, making this bonding technique suitable for applications with certain demands on gas-tightness.
 REFERENCE COUNT: 6 THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 9 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2004154893 CAPLUS
 DOCUMENT NUMBER: 140:348345
 TITLE: Rare-earth-enabled universal solders for microelectromechanical systems and optical packaging
 AUTHOR(S): Jin, Sungho
 CORPORATE SOURCE: University of California at San Diego, La Jolla, CA, 92093-0411, USA
 SOURCE: Journal of Electronic Materials (2003), 32(12), 1366-1370
 CODEN: JECMA5; ISSN: 0361-5225
 PUBLISHER: Minerals, Metals & Materials Society
 DOCUMENT TYPE: Journal
 LANGUAGE: English
 AB In packaging of microelectromech. systems (MEMS), optical, and electronic devices, there is a need to directly bond a wide variety of inorg. materials, such as oxides, nitrides, and semiconductors. Such applications involve hermetic-sealing components, three-dimensional MEMS assembly components as well as active semiconductor or optical components, dielec. layers, diffusion barriers, waveguides, and heat sinks. These materials are known to be difficult to wet and bond with low melting-point solders. New Sn-Ag- or Au-Sn-based universal solders doped with a small amount of rare-earth (RE) elements were developed, which now allow direct and powerful bonding onto the surfaces of various MEMS, optical, or electronic device materials. The microstructure, interface properties, and mech. behavior of the bonds as well as the potential packaging applications of these new solder materials for MEMS and optical fiber devices are described. Various packaging-related structural, thermal, or elec. issues in MEMS are also discussed.

REFERENCE COUNT: 16 THERE ARE 16 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 10 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 20031991807 CAPLUS
 DOCUMENT NUMBER: 140:51741
 TITLE: Methods for depositing, releasing, and packaging microelectromechanical devices on wafer substrates
 INVENTOR(S): Patel, Satyadev; Huibers, Andrew; Richards, Peter; Shi, Hongqin; Chiang, Steve; Duboc, Robert, Jr.; Grobelny, Thomas; Dehlinger, Dietrich; Sun, Anthony; Chen, Hung Nai
 PATENT ASSIGNEE(S): Reflectivity, Inc., USA
 SOURCE: PCT Int. Appl., 44 pp.
 CODEN: PXXXD2
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 20
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2003105198	A1	20031218	WO 2003-US18741	20030611
<--				
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SC, SE, SG, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZM, ZW	A1	20050407	US 2002-167361	20020611
US 20050074919	B2	20071211		
US 7307775				
AU 2003263744	A1	20031222	AU 2003-263744	20030611
<--				
CN 1659684	A	20050824	CN 2003-813553	20030611
JP 2005534048	T	20051110	JP 2004-512176	20030611
EP 1666663	A1	20070328	EP 2003-817376	20030611
R: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LI, LU, MC, NL, PT, RO, SE, SI, SK, TR	A2	20041028	WO 2004-US9221	20040324
<--				
WO 2004093083	A3	20050609		
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZM, ZW	A2	20060104	EP 2004-758968	20040324
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK	A	20060607	CN 2004-8012015	20040324
CN 1784748	A	20060607	US 2002-167361	A 20020611

PRIORITY APPLN. INFO.: US 2000-254043P P 20001207
 US 2001-276222P P 20010315

L2 ANSWER 10 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN (Continued)
 US 2001-5308 A2 20011203
 US 2003-407061 A 20030402
 WO 2003-US18741 W 20030611
 WO 2004-US9221 W 20040324
 AB The present invention provides methods for making microelectromech. devices on a wafer. The subject matter of the present invention is related to manufacturing multiple MEMS devices on a wafer, releasing the MEMS structures by removing a sacrificial material, bonding the wafer to another wafer, singulating the wafer assembly, and packaging each wafer assembly portion with one or more MEMS devices thereon, without damaging the MEMS microstructure thereon. A wide variety of microelectromech. devices (MEMS) devices can be made including accelerometers, DC relay and RF switches, optical cross connects and optical switches, microlenses, reflectors and beam splitters, filters, oscillators and antenna system components, variable capacitors and inductors, switched banks of filters, resonant comb-drives and resonant beams, and micromirror arrays for direct view and projection displays. A projection system, a spatial light modulator, and a method for forming a MEMS device are disclosed. The spatial light modulator can have 2 substrates bonded together with 1 of the substrates comprising a micromirror array. The 2 substrates can be bonded at the wafer level after depositing a getter material and/or solid or liquid lubricant on 1 or both of the wafers. The wafers can be bonded together hermetically if desired, and the pressure between the 2 substrates can be below atmospheric.
 REFERENCE COUNT: 9 THERE ARE 9 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 11 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2003:939755 CAPLUS
 DOCUMENT NUMBER: 141:95809
 TITLE: Beginning-to-end wafer bonding for advanced optical systems
 AUTHOR(S): Farrens, Shari N.; Lindner, Paul; Dwyer, Steven; Wimpflinger, Markus
 CORPORATE SOURCE: EV Group Inc., Phoenix, AZ, 85034, USA
 SOURCE: Proceedings of SPIE-The International Society for Optical Engineering (2003), 5177(Gradient Index, Miniature, and Diffractive Optical Systems III), 31-36
 CODEN: PSISDG; ISSN: 0277-786X
 PUBLISHER: SPIE-The International Society for Optical Engineering
 DOCUMENT TYPE: Journal; General Review
 LANGUAGE: English
 AB A review. The old adage "work smarter, not harder" is certainly applicable in today's competitive marketplace for optical MEMS. To survive the current economic conditions, high volume manufacturers must get optimum performance and yield from each design and manufactured component. Wafer bonding, and its numerous variants, is entering mainstream production environments by providing solns. throughout the production flow. For example, SOI (Si on insulator) and other laminated materials such as GaAs/Si are used as cost effective alternatives to mol. epitaxy methods for Bragg mirrors, r.f. resonators, and hybrid device fabrication. Temporary wafer bonding is used extensively to allow fragile compound semiconductors to be attached to rigid support wafers. This allows for front side and backside processing with a reduction in wafer breakage and increases in thickness uniformity results after backgrinding operations. Permanent wafer bonding is used to attach compound semiconductors to each other or Si to completely integrate optical components and logic or MEMS components. Permanent hermetic sealing is used for waveguide formation and, when combined with vacuum sealing, higher performance is achieved for r.f. resonators. Finally, many of the low temperature solders and eutectic alloys are finding application in wafer-to-wafer level packaging of optical devices to ceramic packages. Through clever application of these bonding methods, throughput increases and reduction in fabrication complexity givs a clear edge in the market place. This presentation will provide guidelines and process overviews needed to adopt wafer-to-wafer bonding technologies into the high volume-manufacturing environment.
 REFERENCE COUNT: 3 THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 12 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2003:787533 CAPLUS
 DOCUMENT NUMBER: 140:189601
 TITLE: Drift-free, 1000G mechanical shock tolerant single-crystal silicon two-axis MEMS tilting mirrors in a 1000x1000-port optical crossconnect
 AUTHOR(S): Simon, M. E.; Pardo, F.; Chan, H. B.; Kim, J.; Gates, J.; Kraus, J. S.; Goyal, S.; Carr, D.; Kleiman, R.
 CORPORATE SOURCE: Bell Laboratories, Lucent Technologies, Murray Hill, NJ, 07374, USA
 SOURCE: Trends in Optics and Photonics (2003), 86(Optical Fiber Communications Conference, 2003), PD36/1-PD36/3
 CODEN: TOPR88
 PUBLISHER: Optical Society of America
 DOCUMENT TYPE: Journal
 LANGUAGE: English
 AB The authors report drift-free two-axis tilting MEMS mirrors fabricated from single crystal Si. These micromirrors survive 1000G mech. shocks and exhibit angular stability better than 4 millidegrees under simulated office vibrations. Two hermetically sealed mirror arrays were used to build a low-loss nonblocking 1000+1000-port optical cross-connect switch.
 REFERENCE COUNT: 10 THERE ARE 10 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 13 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2003:741399 CAPLUS
 DOCUMENT NUMBER: 140:311594
 TITLE: Packaging of optical MEMS devices
 AUTHOR(S): Low, Yee L.; Scotti, Ronald E.; Ramsey, David A.; Bolle, Cristian A.; O'Neill, Steven P.; Nguyen, Khanh C.
 CORPORATE SOURCE: Lucent Technologies Bell Labs, Murray Hill, NJ, 07974, USA
 SOURCE: Journal of Electronic Packaging (2003), 125(3), 325-328
 CODEN: JEPAA4; ISSN: 1043-7398
 PUBLISHER: American Society of Mechanical Engineers
 DOCUMENT TYPE: Journal
 LANGUAGE: English
 AB Recently, optical MEMS devices have gained considerable attention in the telecommunications industry-particularly in the optical networking and switching arenas. Since optical MEMS are micro-systems which rely on high precision optics, electronics and mechanics working in close concert, these emerging devices pose some unique packaging challenges yet to be addressed by the general packaging industry. Optical MEMS packages often are required to provide both optical and elec. access, hermeticity, mech. strength, dimensional stability, and long-term reliability. Hermetic optical access necessitates the use of metalized and anti-reflection coated windows, and ever-increasing elec. I/O count has prompted the use of higher d. substrate/package technologies. Taking these requirements into consideration, we explore three ceramic packaging technologies, namely high-temperature co-fired ceramic (HTCC), low-temperature co-fired ceramic (LTCC), and thin-film ceramic technologies. In this paper, we describe some optical MEMS packages designed using these three technologies and discuss their substrate designs, package materials, ease of integration and assembly.
 REFERENCE COUNT: 6 THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 14 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2003:603909 CAPLUS
 DOCUMENT NUMBER: 139:126140
 TITLE: Packaging micromechanical devices
 INVENTOR(S): Low, Yee Leng; Ramsey, David Andrew
 PATENT ASSIGNEE(S): Lucent Technologies Inc., USA
 SOURCE: U.S. 6 pp.
 CODEN: USXXAM
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 6603182	Bl	20030805	US 2002-97072	20020312

 <--
 PRIORITY APPLN. INFO.: US 2002-97072 20020312
 AB The specification describes a packaging arrangement for micro-electromech. systems (MEMS). The MEMS devices are mounted on a ceramic platform and are then packaged in a hybrid package. The hybrid package may be hermetically sealed. The hybrid package uses a ceramic insert as the primary MEMS device enclosure. The ceramic insert is mounted on a polymer printed wiring board, which provides both support and elec. interconnection for the ceramic insert. Optical access to the MEMS device is through a transparent window that may be hermetically sealed to the ceramic insert. The use of a ceramic primary enclosure for the MEMS device array substantially eliminates thermomech. instabilities and provides thermomech. and hermetic performance for the elements that require it. The main interconnection and routing function, implemented using standard epoxy resin printed circuit technol., yields high interconnection versatility and performance at low cost.
 REFERENCE COUNT: 8 THERE ARE 8 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 15 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2003:453862 CAPLUS
 DOCUMENT NUMBER: 139:172091
 TITLE: Tailoring of stress development in MEMS
 packaging systems
 AUTHOR(S): Walwadkar, Satyajit S.; Cho, Junghyun; Farrell, P. W.; Felton, Lawrence E.
 CORPORATE SOURCE: Dept. of Mechanical Engineering, State University of New York, Binghamton, NY, 13902-6000, USA
 SOURCE: Materials Research Society Symposium Proceedings (2003), Volume Date 2002, 741(Nano- and Microelectromechanical Systems (NEMS and MEMS) and Molecular Machines), 139-144
 PUBLISHER: Materials Research Society
 DOCUMENT TYPE: Journal
 LANGUAGE: English
 AB A better understanding of the origin and evolution of the stresses is a crucial step in improving reliability of packaging systems for microelectromech. systems (MEMS). Given its importance, the authors examine the stresses developed in hermetically packaged MEMS inertial sensors. For this purpose, an optical surface profilometer is employed to assess the stresses by measuring the curvature of dummy Si dies (3.5x3.5 mm²) assembled in different types of packages and die attach adhesives. The authors also explore a temporal evolution of stresses during thermal exposure of the test packages in an effort to emulate actual packaging processes and device operation conditions. The result shows different levels of stresses generated from various adhesives and package types, and also a stress evolution during packaging processes. The mech. stress data also show a good agreement with MEMS performance data obtained from actual accelerometers. Therefore, the stress data will not only be useful in better understanding performance of MEMS packages, but the testing protocol can also provide a diagnostic tool for very small packaging systems.
 REFERENCE COUNT: 14 THERE ARE 14 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 17 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2003:95369 CAPLUS
 DOCUMENT NUMBER: 139:93537
 TITLE: Conductive interconnections through thick silicon substrates for 3D packaging
 AUTHOR(S): Takizawa, Takashi; Yamamoto, Satoshi; Itoi, Kazuhisa; Suematsu, Tatsuo
 CORPORATE SOURCE: Electron Device Laboratory, Fujikura Ltd., Koto-Ward, Tokyo, 135-8512, Japan
 SOURCE: IEEE International Conference on Micro Electro Mechanical Systems, Technical Digest, 15th, Las Vegas, NV, United States, Jan. 20-24, 2002 (2002), 388-391. Institute of Electrical and Electronics Engineers: New York, N. Y.
 CODEN: 69DOEU; ISBN: 0-7803-7185-2
 DOCUMENT TYPE: Conference
 LANGUAGE: English
 AB We have developed key technologies to form conductive interconnections through a thick Si substrate, which are potentially applied for 3D device fabrication or packaging of optical MEMS devices. We demonstrate to form metal filled through-holes (THs) in thick Si substrates (\approx 500 μ m) mainly using photoassisted electrochem. etching (PAECE) and molten metal suctioned method (MMSM). The THs that we exptl. made with these technologies had 15 μ m in the diameter and the aspect ratio of 35. The maximum d. was 500 THs/cm². The dielec. breakdown voltage of the THs was >500 V. In the result of a radioisotope leak test using 85Kr, the leakage rate of THs between the front and the back of the substrate was lower than the detection limit ($1 + 10^{-15}$ Pa·m³/s.).
 REFERENCE COUNT: 4 THERE ARE 4 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 16 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2003:372006 CAPLUS
 TITLE: Device for the hermetic encapsulation of a component that must be protected against all stresses
 AUTHOR(S): Val, Christian
 PATENT ASSIGNEE(S): 3D Plus, Fr.
 SOURCE: PCT Int. Appl.
 DOCUMENT TYPE: Patent
 LANGUAGE: French
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2003041163	A1	20030515	WO 2002-FR3524	20021015

<--
 W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, LZ, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UC, US, UZ, VN, YU, ZA, ZM, ZW, AT, BE, BG, RW: GH, GN, KE, LS, MW, MZ, SD, SL, TZ, UG, ZM, ZW, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG
 AU 2002350840 A1 20030519 AU 2002-350840 20021015
 <-- EP 1442480 A1 20040804 EP 2002-785549 20021015
 <-- R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK, JP 20050508763 T 20050407 JP 2003-543098 20021015
 PRIORITY APPLN. INFO.: FR 2001-14543 A 20011109
 WO 2002-FR3524 W 20021015
 AB The invention relates to a device that is used for the hermetic encapsulation of a component that must be protected against all stresses. The aforementioned component (5) is fixed to a substrate (15) having a temperature control element (17) glued (16) to the other face thereof. Said assembly is disposed in a case comprising two parts (11, 12) which are assembled by means of gluing (13), with a passage for optical links (6) and elec. connections (18, 142). Said component is supported by elements (19) which project out from one part (11) of the case. A unit (14) is glued to the other part (12) of the case, said unit comprising three-dimensional interconnections which form the temperature regulation electronics. The aforementioned unit, case (11, 12) and a min. length (L) of the links and connections are encased in a mineral protective layer (4'). In particular, the invention can be used for optoelectronic components and MEMS components.
 REFERENCE COUNT: 8 THERE ARE 8 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 18 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2003:67643 CAPLUS
 DOCUMENT NUMBER: 139:44474
 TITLE: A new approach for opto-electronic/MEMS packaging
 AUTHOR(S): Keusseyan, R.; Sosnowski, J.; Doyle, M.; Amey, D.; Horowitz, S.
 CORPORATE SOURCE: DuPont i Technologies, Research Triangle Park, NC, 27709, USA
 SOURCE: Proceedings - Electronic Components & Technology Conference (2002), 52nd, 259-261
 CODEN: PETCSE
 PUBLISHER: Institute of Electrical and Electronics Engineers
 DOCUMENT TYPE: Journal; General Review
 LANGUAGE: English
 AB A review. Optoelectronic and MEMS packages require unique capabilities over and above traditional hermetic multichip modules. In addition to hermeticity or vacuum atmospheric, optoelectronic systems require direct input/output of optical, r.f. and other sensitive signals through the package using fiber-optic, coaxial and/or other interconnection approaches. Precise optical component alignment and accurate thermal management is critical to achieve component and system performance capabilities. Furthermore, to improve MEMS functionality, performance and service life, a suitable getter and/or dopant is required compatible with the hermetic /vacuum package atmospheric. The getter/dopant is usually activated after achieving hermetic or vacuum atmospheric. A comprehensive MEMS packaging approach is introduced based on photo-patterned thick film metalization, LTCC, brazing technol. and new feed-through approaches. The new methodol. incorporates most reported MEMS packaging requirements for proven performance, reliability, low cost and mass production capabilities.

L2 ANSWER 19 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2002:906797 CAPLUS
 DOCUMENT NUMBER: 138:10600
 TITLE: Radio frequency microelectromechanical systems
 devices
 on low-temperature co-fired ceramic substrates
 INVENTOR(S): Ozgur, Mehmet; Huff, Michael A.
 PATENT ASSIGNEE(S): Corporation for National Research Initiatives, USA
 SOURCE: PCT Int. Appl., 141 pp.
 CODEN: PIXXD2
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2002096166	A1	20021128	WO 2002-US15602	20020520
<-- WO 2002096166 A9 20030130				
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, ME, MK, MN, MM, MR, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TZ, TM, TN, TR, TT, TZ, UA, UG, UZ, VN, YU, ZA, ZM, ZW				
RN: GH, GM, KE, LS, MW, MZ, SD, SL, TZ, UG, ZM, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GR, IE, IT, LU, MC, NL, PT, SE, TR, BT, BJ, CF, CG, CI, CM, GA, GN, GQ, GN, ML, MR, NE, SN, TD, TG				
AU 200232008 A1 2002-322008 AU 2002-322008 20020520				
<-- US 20030020173 A1 20030130 US 2002-147907 20020520				
<-- US 6815739 B2 20041109				
US 20050167047 A1 20050804 US 2003-663986 20030917				
US 7045440 B2 20060516				
US 20040262645 A1 20041230 US 2004-835590 20040430				
<-- US 7012327 B2 20060314				
US 20050161753 A1 20050728 US 2005-52302 20050208				
US 2001-291647P P 20010518				
US 2002-147907 A3 20020520				
WO 2002-US15602 W 20020520				
US 2004-835590 A3 20040430				

PRIORITY APPLN. INFO.:

AB A phased-array antenna system and other types of radio frequency (RF) devices and systems using microelectromech. switches (MEMS) and low-temperature co-fired ceramic (LTCC) technol. and a method of fabricating such phased-array antenna system and other types of radio frequency (RF) devices are disclosed. Each antenna or other type of device includes ≥2 multilayer ceramic modules and a MEMS device fabricated on 1 of the modules. Once fabrication of the MEMS device is completed, the 2 ceramic modules are bonded together, hermetically sealing the MEMS device, as well as allowing elec. connections between all device layers. The bottom ceramic module has also cavities at the backside for mounting integrated circuits.

L2 ANSWER 20 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2002:817919 CAPLUS
 DOCUMENT NUMBER: 138:27973
 TITLE: Low-temperature anodic bonding facilitated by lithium-exchanged sodium borosilicate glass
 AUTHOR(S): Watson, Chad S.; Hirschfeld, Deidre A.; Schubert, W. Kent
 CORPORATE SOURCE: New Mexico Institute of Mining and Technology, Socorro, NM, 87301, USA
 SOURCE: Ceramic Engineering and Science Proceedings (2002), 23(4), 877-884
 CODEN: CESPDK; ISSN: 0196-6219
 PUBLISHER: American Ceramic Society
 DOCUMENT TYPE: Journal
 LANGUAGE: English
 AB A critical issue during the hermetic packaging of microelectro-mech. system (MEMS) devices was the need for lower glass-to-silicon bonding temps. Ion exchange, a technique traditionally used to modify the mech. and optical properties of glasses, was employed to reduce the temperature typically required to anodically bond glass to silicon. Lithium ion exchange techniques were used to lower the anodic bonding temperature to as low as 230° using a point-cathode configuration and to 200° using a com. bonder.
 REFERENCE COUNT: 16 THERE ARE 16 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 19 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN (Continued)
 The internal layers are formed using conducting, resistive and high-k dielec. pastes available in std. LTCC fabrication and low-loss dielec. LTCC tape materials.
 REFERENCE COUNT: 6 THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 21 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2002:766978 CAPLUS
 DOCUMENT NUMBER: 138:63551
 TITLE: Performance and reliability of a MEMS-based tunable optical filter operating in the 1565 nm-1525 nm wavelength range
 AUTHOR(S): Sriram, T. S.; Strauss, B.; Pappas, S.; Baliga, A.; Jean, A.; Parodos, T.; Dietz, D.; Wang, F.; Azimi, M.; McCallion, K.; Vakkashoori, D.
 CORPORATE SOURCE: Boston Optical Components, Nortel Networks, Wilmington, MA, 01887, USA
 SOURCE: Materials Research Society Symposium Proceedings (2002), 722(Materials and Devices for Optoelectronics and Microphotronics), 149-154
 CODEN: MRSPDH; ISSN: 0272-9172
 PUBLISHER: Materials Research Society
 DOCUMENT TYPE: Journal
 LANGUAGE: English
 AB This paper describes the results of extensive performance and reliability characterization of a Si-based surface micro-machined tunable optical filter. The device comprises a high-finesse Fabry-Perot etalon with one flat and one curved dielec. mirror. The curved mirror is mounted on an electrostatically actuated Si nitride membrane tethered to the substrate using Si nitride posts. A voltage applied to the membrane allows the device to be tuned by adjusting the length of the cavity. The device is coupled optically to an input and an output single mode fiber inside a hermetic package. Extensive performance characterization (over operating temperature range) was performed on the packaged device. Parameters characterized included tuning characteristics, insertion loss, filter line-width and side mode suppression ratio. Reliability testing was performed by subjecting the MEMS structure to a very large number of actuations at an elevated temperature both inside the package and on a test board. The MEMS structure is extremely robust, running trillions of actuations without failures. Package level reliability testing conforming to Telcordia stds. indicated that key device parameters including insertion loss, filter line-width and tuning characteristics did not change measurably over the duration of the test.
 REFERENCE COUNT: 7 THERE ARE 7 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 22 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 20021599014 CAPLUS
 DOCUMENT NUMBER: 138:31697
 TITLE: A high reliability, reworkable, fluorinated poly(phenylene ether ketone) (12F-PEK) coating for MOEMS and optical systems packaging
 AUTHOR(S): Pike, R. T.; Adkins, C. L.; Newton, C. M.; Bryant, C. E.
 CORPORATE SOURCE: Microsystems Technology Group, Harris Corporation, Palm Bay, FL, 32902, USA
 SOURCE: Proceedings - International Advanced Packaging Materials Symposium, 8th, Stone Mountain, GA, United States, Mar. 3-6, 2002 (2002), 326-330.
 Institute of Electrical and Electronics Engineers:
 New York, N. Y.
 CODEN: 69CYRY; ISBN: 0-7803-7434-7
 DOCUMENT TYPE: Conference
 LANGUAGE: English
 AB A fluorinated poly(phenylene ether ketone) encapsulant was identified as a high-performance chemical reworkable thermoplastic with near hermetic protection. The 12F-PEK has legacy as a high-reliability microelectronics coating for bare Si and GaAs die and microelectronics packages including PEM, CSP, PCB, COB, SCM, MCM, and MEMS. It has recently been discovered that the 12F-PEK coating is a peripheral packaging candidate for MOEMS, electrooptical, and micro-scale optical applications. Characterization of the 12F-PEK encapsulant revealed a refractive index of 1.51 from 200-900 nm, <5% haze from 350-800 nm, >90% transmission from 1000-2100 nm, 0.07% moisture absorption, and no failures at 85°/85% RH/5V bias/2500 h with Sandia ATC 2.6 TVs. The low water absorption and long-term stability of the 12F-PEK fluoropolymer presents a novel approach for packaging optical systems that will be subjected to hostile environmental conditions.
 REFERENCE COUNT: 4 THERE ARE 4 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE
 FORMAT

L2 ANSWER 23 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 20021465131 CAPLUS
 TITLE: Enclosure for mems apparatus and method of using the same
 INVENTOR(S): Daneman, Michael J.; Behin, Behrang; Wall, Franklin
 PATENT ASSIGNEE(S): Onix Microsystems, Inc, USA
 SOURCE: U.S. Pat. Appl. Publ.
 CODEN: USXXCO
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 6
 PATENT INFORMATION:
 PATENT NO. KIND DATE APPLICATION NO. DATE
 US 20020075551 A1 20020620 US 2001-989905 20011120
 <-- WO 2001077007 A1 20011018 WO 2001-US11046 20010404
 <-- W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CR, CU, CZ, DE, DK, DM, DZ, EE, ES, FI, GB, GD, GE, GH, GM, HR, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, UZ, VN, YU, ZA, ZW
 RW: GH, GN, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG
 WO 2002091464 A1 20021114 WO 2002-US9038 20020301
 <-- W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MW, MX, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, UZ, VN, YU, ZA, ZW
 RW: GH, GN, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG
 AU 2002252486 A1 20021118 AU 2002-252486 20020301
 <-- US 7183633 B2 20070227 US 2004-469516 20040527
 PRIORITY APPLN. INFO.: US 2000-250237P P 20001129
 <-- WO 2001-US11046 W 20010404
 <-- WO 2001-US11047 W 20010404
 <-- US 1999-123496P P 19990309
 <-- WO 2000-US5744 A 20000302
 <-- US 2000-546432 A 20000410
 <-- US 2001-798129 A 20010301
 <-- US 2001-851587 A 20010508
 <-- US 2001-853868 A 20010511

L2 ANSWER 23 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN (Continued)
 US 2001-853869 A 20010511
 US 2001-853870 A 20010511
 US 2001-891760 A 20010625
 US 2001-303755P P 20010707
 US 2001-900841 A 20010707
 US 2001-949210 A 20010907
 US 2001-992530 A 20011106
 US 2001-992531 A 20011106
 US 2001-989905 A 20011120
 WO 2002-US9038 W 20020301

AB An enclosure for sealing a MEMS optical device, a MEMS apparatus, a MEMS module, and a method for switching optical signals are disclosed. The enclosure includes one or more sidewalls and an optical element hermetically sealed to at least one of the sidewalls. Suitable optical elements include windows, lenses and lens arrays. The enclosure may be evacuated to improve the performance of the MEMS device enclosed within it. The MEMS apparatus includes a MEMS device enclosed by an enclosure of the type described above. The MEMS device may include a substrate and the enclosure may be bonded to the substrate. Alternatively, the MEMS device may include a substrate attached to a mount and the enclosure may be bonded to the mount. The MEMS module includes a mount and a MEMS device attached to the mount. One or more optical fibers are attached to the mount proximate the MEMS device. An enclosure, attached to the mount encloses the MEMS device. The fibers are located outside the enclosure. Optical signals may be coupled between the fibers and the MEMS device within the enclosure through an optical elements in the sidewall. The optical switching method proceeds by reducing a pressure of an atmosphere proximate the MEMS optical device and moving at least one of the optical elements from a first position to a second position. The optical element deflects an optical signal when it is in the second position.

L2 ANSWER 24 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2002453290 CAPLUS
 DOCUMENT NUMBER: 137:39633
 TITLE: High aspect ratio through-hole interconnections in silicon substrates
 AUTHOR(S): Suematsu, T.; Itoh, K.; Yamamoto, S.; Takizawa, T.
 CORPORATE SOURCE: Electron. Device Res. Lab., Fujikura Ltd., Japan
 SOURCE: Fujikura Gihou (2002), 102, 53-57
 CODEN: FUGIEH; ISSN: 0912-2761
 PUBLISHER: Fujikura
 DOCUMENT TYPE: Journal; General Review
 LANGUAGE: Japanese
 AB A review. We have developed key technologies to form conductive interconnections through a thick Si substrate, which are potentially applied for 3-dimensional stacking of semiconductor devices or packaging of Micro Optical Electro-Mech. System (MOEMS) devices. We demonstrate to form metal filled Through-Holes (THs) in thick Si (Si) substrates ($t = \text{approx. } 500 \mu\text{m}$) mainly using Photo Assisted Electro-Chemical Etching (PAECE) and Molten Metal Suctioned Method (MMSM). The THs had $15 \mu\text{m}$ in the diameter and the aspect ratio of 35. And the maximum d . was 500 THs/cm^2 . The dielec. breakdown voltage of the TH was $>500 \text{ V}$. In result of a radioisotope leak test using Kr-85, the leakage rate of THs between the front and the back of the substrate was lower than the limit of detection ($1 + 10^{-15} \text{ Pa.m/s}$).

L2 ANSWER 25 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2002:376067 CAPLUS
 DOCUMENT NUMBER: 137:86315
 TITLE: Getters: micromolecular scavengers for packaging
 AUTHOR(S): Previti, Mike; Gilleo, Ken
 CORPORATE SOURCE: Cockson Semiconductor Packaging Materials, Foxborough, MA, USA
 SOURCE: Proceedings - International Symposium on Advanced Packaging Materials: Processes, Properties and Interfaces, Braselton, GA, United States, Mar. 11-14, 2001 (2001), Meeting Date 2001, 201-206, Institute of Electrical and Electronics Engineers: New

York, N. Y.
 CODEN: 69CPT9; ISBN: 0-930815-64-5

DOCUMENT TYPE: Conference; General Review

LANGUAGE: English

AB A review on the use of various types of getters for microelectromechanical (MEMS) devices. Dual-purpose moisture particle getters are ideal and are already used in some optical microelectromechanical (MEMS) com. products. However, more work needs to be done in this area, especially for quasi-hermetic packaging.

REFERENCE COUNT: 16 THERE ARE 16 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE

FORMAT

L2 ANSWER 26 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2001:864735 CAPLUS
 DOCUMENT NUMBER: 135:379905
 TITLE: Packaging micromechanical devices in all-silicon chamber
 INVENTOR(S): Degani, Yinon; Dudderar, Thomas Dixon; Tai, King Lien
 PATENT ASSIGNEE(S): Lucent Technologies Inc., USA
 SOURCE: Eur. Pat. Appl., 8 pp.
 CODEN: EPXXDW

DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1157967	A2	20011128	EP 2001-304276	20010514
EP 1157967	A3	20030102		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
CA 2342409	A1	20011122	CA 2001-2342409	20010329
TW 536523	B	20030611	TW 2001-90111671	20010516
JP 2002043449	A	20020208	JP 2001-151776	20010522
JP 3424926	B2	20030707	US 2000-575883	A 20000522

PRIORITY APPLN. INFO.: US 2000-575883 A 20000522

AB The specification describes packaging assemblies for micro-electronic machined mech. systems (MEMS). The MEMS devices in these package assemblies are based on Si MEMS devices on a Si support and the MEMS devices and the Si support are mech. isolated from foreign materials. Foreign materials pose the potential for differential thermal expansion that deleteriously affects optical alignment in the MEMS devices. In a preferred embodiment the MEMS devices are enclosed in an all-Si chamber. Mech. isolation is also aided by using a pin contact array for interconnecting the Si support substrate for the MEMS devices to the next interconnect level. The use of the pin contact array also allows the MEMS devices to be easily demountable for replacement or repair.

REFERENCE COUNT: 3 THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE

FORMAT

L2 ANSWER 27 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2001:728570 CAPLUS
 DOCUMENT NUMBER: 136:28303
 TITLE: Stress analysis of silicon membranes with electropolished permalloy films using Raman scattering
 AUTHOR(S): Cho, Hyoung J.; Oh, Kwang W.; Ahn, Chong H.; Boolchand, P.; Nam, Tae-Chul
 CORPORATE SOURCE: Department of Electrical and Computer Engineering and Computer Science, University of Cincinnati, Cincinnati, OH, 45221-0030, USA
 SOURCE: IEEE Transactions on Magnetics (2001), 37(4, Pt. 1), 2749-2751
 CODEN: IEMQAQ; ISSN: 0018-9464
 PUBLISHER: Institute of Electrical and Electronics Engineers
 DOCUMENT TYPE: Journal
 LANGUAGE: English
 AB The authors have measured the stress profile on a Si membrane electropolished with a permalloy film using Raman scattering. The effect of Si membrane thickness and permalloy film thickness on stress distribution was studied. Depending upon the nature of stress, the optic phonon in Si at 520 cm⁻¹ either shifts upward (compressive) or downward (tensile). The phonon frequency shift is proportional to the magnitude of stress. A microscope X-Y stage was used to map the stress distribution over the Si membrane that was covered and uncovered by the permalloy film.
 Si membranes in the thickness range, 9 μ m < t_m < 12 μ m, and permalloy films in the thickness range, 6 μ m < t_p < 13 μ m showed evidence of compressive stress. Based on the present results, membrane type microvalve design is optimized to prevent leakage, originating from stressed membranes. Such a nondestructive and noncontact microscopic stress anal. technique can be applied for design optimization in various magnetic MEMS devices.

REFERENCE COUNT: 6 THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE

FORMAT

L2 ANSWER 28 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2001:722439 CAPLUS
 DOCUMENT NUMBER: 135:380013
 TITLE: Thermal evolution of the magnetization in nanocrystalline Fe particles investigated by electron holography
 AUTHOR(S): Bonatti, E.; Del Bianco, L.; Pasquini, L.; Matteucci, G.; Beeli, C.; Signoretto, S.
 CORPORATE SOURCE: Department of Physics, University of Bologna and National Institute for the Physics of Matter (INFM), Bologna, I-40127, Italy
 SOURCE: Journal of Applied Physics (2001), 90(8), 4152-4158
 CODEN: JAPIAU; ISSN: 0021-8979
 PUBLISHER: American Institute of Physics
 DOCUMENT TYPE: Journal
 LANGUAGE: English
 AB Micrometric, irregularly shaped Fe particles with a nanocrystalline structure have been prepared by mech. attrition through ball-milling. Electron holog. has been employed to visualize the stray field emerging from isolated Fe particles, both at 300 K and at selected temps. T \leq 1200 K, from which indirect information on the magnetic domain configuration has been inferred. By complementary x-ray diffraction and TEM studies a relation has been established between the changes of the leakage field and of the microstructure upon annealing; the structural evolution is accompanied by strong modifications in the interior magnetization pattern. This relation finds explanation in the framework of the random anisotropy model, including temperature-induced reversible variations in the exchange correlation length and saturation magnetization. Also, the role played by the overall geometrical features of the particles in the determination of the actual domain configuration has been studied.

REFERENCE COUNT: 23 THERE ARE 23 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE

FORMAT

L2 ANSWER 29 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 1998:190952 CAPLUS
 DOCUMENT NUMBER: 128:263670
 ORIGINAL REFERENCE NO.: 128:52069a,52072a
 TITLE: Low temperature packaging of CMOS infrared
 microsystems by Si-Al-Au bonding
 AUTHOR(S): Waelti, M.; Schneeberger, N.; Paul, O.; Baltes, H.
 CORPORATE SOURCE: Physical Electronics Laboratory, ETH Zurich, Zurich,
 CH-8093, Switz.
 SOURCE: Proceedings - Electrochemical Society (1998
), 97-36(Semiconductor Wafer Bonding: Science,
 Technology, and Applications), 147-154
 CODEN: PESODO; ISSN: 0161-6374
 PUBLISHER: Electrochemical Society
 DOCUMENT TYPE: Journal
 LANGUAGE: English
 AB A new low temperature packaging method for MEMS is reported. It is
 demonstrated with the encapsulation of a CMOS IR detector microsystem.
 An IR filter is directly attached to the sensor die using an on-chip Au
 spacer frame electroplated by standard bumping technol. Delicate
 components such as circuitry and IR pixels are hermetically sealed off and
 effectively screened from undesired influences. The process is based on
 the diffusion bonding of the Si filter onto the Au spacer using 1 μ m of
 sputtered Al. Annealing at 350° for 33 min under a bonding
 pressure of 45 MPa produces bonds with a shear strength larger than 70
 MPa. The bonding zone consists of an AuAl intermetallic layer. Thermal
 aging at 155° for 1000 h shows no changes in the interface
 metallurgy. The method is generally suited for integrated microsystems
 requiring hermetic packaging.
 REFERENCE COUNT: 12 THERE ARE 12 CITED REFERENCES AVAILABLE FOR
 THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE
 FORMAT

L2 ANSWER 30 OF 30 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 1995:952034 CAPLUS
 TITLE: Packaging of microfabricated devices and systems
 AUTHOR(S): Ko, Wen H.
 CORPORATE SOURCE: Department of Electrical Engineering and Applied
 Physics, and Electronics Design Center, Case Western
 Reserve University, Cleveland, OH, 44106, USA
 SOURCE: Materials Chemistry and Physics (1995),
 42(3), 169-175
 CODEN: MCHPDR; ISSN: 0254-0584
 PUBLISHER: Elsevier
 DOCUMENT TYPE: Journal
 LANGUAGE: English
 AB All devices and systems need to be packaged for applications. For
 microfabricated devices or systems the packaging is an essential part of
 the design, not an after-thought. The functions of packaging are: (i) to
 protect the devices from the environment, and (ii) to protect the
 environment from the device operation. At present, there is no generally
 applicable packaging method for all microdevices, but there are basic
 principles useful in packaging design. This article outlines the
 fundamental requirements, design considerations, and packaging techniques
 for sensors and microsystems, with selected examples, and suggested refs.
 The protection of the device includes: (i) elec. isolation and
 passivation
 of leads and device structures from the penetration of moisture and ions;
 sealing techniques and hermeticity measurements are important
 aspects; (ii) mech. protection to ensure structural integrity and
 dimensional stability; (iii) thermal and optical isolation, and
 (i.v.) chemical and biol. isolation and protection. It is also
 necessary to protect the environment from the device materials and device operation,
 so that no undesirable reaction with or contamination of the environment
 occurs. This is especially important for devices used in biomedical,
 pharmaceutical and food processing. Biocompatibility and contamination
 must be considered as factors in the design. Successful packaging design
 requires the integration of knowledge of materials, device
 characteristics, packaging and evaluation techniques. It remains as a
 challenge in the MEMS field for engineers.

=> s (hermetic? or leak?) and (semiconductor or electronic) and (optic? or visual?)
and py<=2004

14143 HERMETIC?
125618 LEAK?
690366 SEMICONDUCTOR
104164 SEMICONDUCTORS
718231 SEMICONDUCTOR

(SEMICONDUCTOR OR SEMICONDUCTORS)

596113 ELECTRONIC
39968 ELECTRONICS
621902 ELECTRONIC

(ELECTRONIC OR ELECTRONICS)

1222552 OPTIC?

152386 VISUAL?

25140108 PY<=2004

L3 1117 (HERMETIC? OR LEAK?) AND (SEMICONDUCTOR OR ELECTRONIC) AND (OPTIC? OR VISUAL?) AND PY<=2004

=> s l3 and (indicat? or sens?)

2488994 INDICAT?

1635367 SENS?

L4 261 L3 AND (INDICAT? OR SENS?)

=> d scan

L4 261 ANSWERS CAPLUS COPYRIGHT 2009 ACS on STN
CC 76-0 (Electric Phenomena)
Section cross-reference(s): 57, 73
TI A new approach for opto-electronic/MEMS packaging
ST review optoelectronic IC packaging ceramic; MEMS packaging ceramic review
IT Micromachines
(microelectromech. devices; new approach for opto-electronic
/MEMS packaging)
IT Ceramics
Electronic packaging materials
Electronic packaging process
Optoelectronic semiconductor devices
(new approach for opto-electronic/MEMS packaging)
IT Integrated circuits
(optoelectronic; new approach for opto-electronic/MEMS
packaging)

HOW MANY MORE ANSWERS DO YOU WISH TO SCAN? (1):0

```
=> s 14 and (gas or fluid)
 1756895 GAS
 573560 GASES
 1956527 GAS
           (GAS OR GASES)
 503698 FLUID
 207273 FLUIDS
 605029 FLUID
           (FLUID OR FLUIDS)
L5      40 L4 AND (GAS OR FLUID)

=> d 15 1-40 ibib abs)
'ABS)' IS NOT A VALID FORMAT FOR FILE 'CAPLUS'
```

The following are valid formats:

```
ABS ----- GI and AB
ALL ----- BIB, AB, IND, RE
APPS ----- AI, PRAI
BIB ----- AN, plus Bibliographic Data and PI table (default)
CAN ----- List of CA abstract numbers without answer numbers
CBIB ----- AN, plus Compressed Bibliographic Data
CLASS ----- IPC, NCL, ECLA, FTERM
DALL ----- ALL, delimited (end of each field identified)
DMAX ----- MAX, delimited for post-processing
FAM ----- AN, PI and PRAI in table, plus Patent Family data
FBIB ----- AN, BIB, plus Patent FAM
IND ----- Indexing data
IPC ----- International Patent Classifications
MAX ----- ALL, plus Patent FAM, RE
PATTS ----- PI, SO
SAM ----- CC, SX, TI, ST, IT
SCAN ----- CC, SX, TI, ST, IT (random display, no answer numbers;
           SCAN must be entered on the same line as the DISPLAY,
           e.g., D SCAN or DISPLAY SCAN)
STD ----- BIB, CLASS

IABS ----- ABS, indented with text labels
IALL ----- ALL, indented with text labels
IBIB ----- BIB, indented with text labels
IMAX ----- MAX, indented with text labels
ISTD ----- STD, indented with text labels

OBIB ----- AN, plus Bibliographic Data (original)
OIBIB ----- OBIB, indented with text labels

SBIB ----- BIB, no citations
SIBIB ----- IBIB, no citations

HIT ----- Fields containing hit terms
HITIND ----- IC, ICA, ICI, NCL, CC and index field (ST and IT)
           containing hit terms
HITRN ----- HIT RN and its text modification
HITSTR ----- HIT RN, its text modification, its CA index name, and
           its structure diagram
HITSEQ ----- HIT RN, its text modification, its CA index name, its
           structure diagram, plus NTE and SEQ fields
```

FHITSTR ----- First HIT RN, its text modification, its CA index name, and its structure diagram
FHITSEQ ----- First HIT RN, its text modification, its CA index name, its structure diagram, plus NTE and SEQ fields
KWIC ----- Hit term plus 20 words on either side
OCC ----- Number of occurrence of hit term and field in which it occurs

To display a particular field or fields, enter the display field codes. For a list of the display field codes, enter HELP DFIELDS at an arrow prompt (=>). Examples of formats include: TI; TI,AU; BIB,ST; TI,IND; TI,SO. You may specify the format fields in any order and the information will be displayed in the same order as the format specification.

All of the formats (except for SAM, SCAN, HIT, HITIND, HITRN, HITSTR, FHITSTR, HITSEQ, KWIC, and OCC) may be used with DISPLAY ACC to view a specified Accession Number.

ENTER DISPLAY FORMAT (BIB):d 15 1-40 ibib abs
'D' IS NOT A VALID FORMAT FOR FILE 'CAPLUS'

The following are valid formats:

ABS ----- GI and AB
ALL ----- BIB, AB, IND, RE
APPS ----- AI, PRAI
BIB ----- AN, plus Bibliographic Data and PI table (default)
CAN ----- List of CA abstract numbers without answer numbers
CBIB ----- AN, plus Compressed Bibliographic Data
CLASS ----- IPC, NCL, ECLA, FTERM
DALL ----- ALL, delimited (end of each field identified)
DMAX ----- MAX, delimited for post-processing
FAM ----- AN, PI and PRAI in table, plus Patent Family data
FBIB ----- AN, BIB, plus Patent FAM
IND ----- Indexing data
IPC ----- International Patent Classifications
MAX ----- ALL, plus Patent FAM, RE
PAT5 ----- PI, SO
SAM ----- CC, SX, TI, ST, IT
SCAN ----- CC, SX, TI, ST, IT (random display, no answer numbers;
 SCAN must be entered on the same line as the DISPLAY,
 e.g., D SCAN or DISPLAY SCAN)
STD ----- BIB, CLASS

IABS ----- ABS, indented with text labels
IALL ----- ALL, indented with text labels
IBIB ----- BIB, indented with text labels
IMAX ----- MAX, indented with text labels
ISTD ----- STD, indented with text labels

OBIB ----- AN, plus Bibliographic Data (original)
OIBIB ----- OBIB, indented with text labels

SBIB ----- BIB, no citations
SIBIB ----- IBIB, no citations

HIT ----- Fields containing hit terms
HITIND ----- IC, ICA, ICI, NCL, CC and index field (ST and IT)

containing hit terms

HITRN -----	HIT RN and its text modification
HITSTR -----	HIT RN, its text modification, its CA index name, and its structure diagram
HITSEQ -----	HIT RN, its text modification, its CA index name, its structure diagram, plus NTE and SEQ fields
FHITSTR -----	First HIT RN, its text modification, its CA index name, and its structure diagram
FHITSEQ -----	First HIT RN, its text modification, its CA index name, its structure diagram, plus NTE and SEQ fields
KWIC -----	Hit term plus 20 words on either side
OCC -----	Number of occurrence of hit term and field in which it occurs

To display a particular field or fields, enter the display field codes. For a list of the display field codes, enter HELP DFIELDS at an arrow prompt (=>). Examples of formats include: TI; TI,AU; BIB,ST; TI,IND; TI,SO. You may specify the format fields in any order and the information will be displayed in the same order as the format specification.

All of the formats (except for SAM, SCAN, HIT, HITIND, HITRN, HITSTR, FHITSTR, HITSEQ, FHITSEQ, KWIC, and OCC) may be used with DISPLAY ACC to view a specified Accession Number.

ENTER DISPLAY FORMAT (BIB):